IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Tox Pictent Application

tant Commissioner for Patents

₩ i**H**gton, D.C. 20231

O Re:

Inventor(s): Janardhanan Anand Subramony, Yoshitaka Yokota, Ramaseshan Suryanarayanan Iyer,

Lee Luo, Aihua Chen

METHODS FOR SILICON OXIDE AND OXYNITRIDE DEPOSITION USING SINGLE WAFER LOW PRESSURE Title:

CVD

Transmitted herewith is the patent application identified above, including:

- Specification, claims and abstract, totaling 35 pages. <u>X</u>
- Drawings totaling 15 pages, Formal X Informal. X
- Unsigned Declaration and Power of Attorney. <u>X</u>

Assignment of the invention to Applied Materials, Inc.

Information Disclosure Statement (IDS)/PTO-1449 with copies of IDS citations.

Check No. 47170 in the amount of \$1370.00

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Fee Items	Claims Filed	Included With Basic Fee	Extra Claims	Fee Rate	Total
Fee Items Total Claims	27	- 20 =	7	X \$18.00	126.00
Thdependent Claims	9	- 3 =	6	X \$84.00	504.00
Basic Filing Fee			· · · · · · · · · · · · · · · · · · ·	\$740.00	\$740.00
TOTAL FEES					\$1370.00

The Commissioner is hereby authorized to charge any additional fees which may be required, or credit any overpayment to XXDeposit Account No. 02-2666. A duplicate copy of this transmittal is enclosed.

Please address all future correspondence to: XX

PATENT COUNSEL APPLIED MATERIALS, INC. **Legal Affairs Department P.O.BOX 450A** Santa Clara, CA. 95052

I hereby certify that this correspondence is being deposited with the United States Postal Service as express mail in an envelope addressed to: Box Patent Application, Assistant Commissioner for Patents, Washington, D.C. 20231.

Respectfully submitted,

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